

Title (en)

Forming method of patterned coating.

Title (de)

Verfahren zur Herstellung einer gemusterten Beschichtung.

Title (fr)

Méthode de formation d'une couche à dessins.

Publication

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Application

EP 90112121 A 19900626

Priority

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Abstract (en)

The invention relates to a method of forming a patterned coating upon a surface of a substrate (10). A plurality of separated magnetic elements (11) are arranged side by side forming an arrayed module (15) of the elements (11). Then, the model (15) is brought in close vicinity of the reverse side of the substrate (10). And then, magnetic paint containing powdery magnetic material is applied to the surface of the substrate (10) to make a wet film thereon. Finally, the wet film is hardened through a baking or drying. A continuous pattern corresponding to the configuration pattern of the module (15) appears on the surface of the substrate (10). Alternatively, a coated substrate may be introduced into a magnetic field while a wet film of magnetic paint is carried thereon.

IPC 1-7

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IPC 8 full level

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CPC (source: EP KR)

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Citation (search report)

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- [AD] PATENT ABSTRACTS OF JAPAN, vol. 6, no. 73, 8 May 1982, page 66 C 101, & JP - A - 57 010 376 (NITSUSHIN SEIKOU K.K.) 19-01-1982
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